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Visit Genus, Inc. at SEMICON West in San Francisco, Booth #2401

ATOMIC AGE BEGINS AS GENUS INTRODUCES ATOMIC LAYER DEPOSITION (ALD) TECHNOLOGY

***Genus LYNX2™* ALD Opens Door to 2004**

SUNNYVALE, Calif., July 13, 1999 – Genus, Inc. (NASDAQ: GGNS), announced a new atomic layer deposition technology that provides a strategic pathway to ultra-thin films for wafer processing into the next century. *LYNX2™* ALD (Atomic Layer Deposition) is offered for demonstration on the Genus *LYNX2* advanced single wafer platform. ALD bridges the gap for ultra-thin film requirements from now till the end of the International Technology Roadmap for Semiconductors (ITRS) industry roadmap horizon. ALD technology provides ultra-thin film solutions for logic and DRAM manufacturers at 0.1-micron feature sizes and beyond (to 2014). Genus is expected to ship ALD in 2000 for advanced R&D environments.

Until now, no known solutions to deposition of ultra-thin films existed beyond 0.1-micron linewidths. The use of ALD, however, enables ultra-thin metal and dielectric films to be deposited on wafers as feature sizes shrink with unprecedented uniformity, conformity and quality. *Lynx2* ALD technology enables the deposition of different materials to be integrated into a single process chamber, providing greater capabilities including future gate stack, advanced capacitor and copper interconnect applications.

"It is very exciting to be able to provide a technology bridge for ultra-thin films at this time, especially as the industry faces a crises in new materials capabilities for gate and capacitor needs," said Tom Seidel, chief technology officer of Genus. "Our leadership in CVD copper-barrier-seed (CBS) is also being extended using ALD technology. ALD technology provides many solutions to the area of the industry roadmap that until now had no known solutions."

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Atomic Age Begins as Genus Leads with Atomic Layer Deposition Technology, page 2

“Genus is determined to maintain a leadership position in the ultra-thin film technology arena,” said William W.R. Elder, chairman and chief executive officer of Genus. We are committed to providing solutions to the problems of our customers. Genus will continue to bridge the technology roadmap, opening the door for now and into the future.”

ALD is available as part of a family of products offered on the Genus *LYNX2*. Proven in high-volume production, the *LYNX2* is a multiple film system with multiple-process module capability and a demonstrated high reliability in advanced manufacturing. Multiple films for the atomic layer deposition of gate, capacitor and copper interconnect are available. Initially, these will include aluminum oxide and tantalum oxide as dielectrics, and titanium nitride, tantalum nitride and tungsten nitride as barriers.

For more information about thin film data including the recently released *LYNX2* RInG (Rapid Integrated Gate) and ultra-thin films for atomic layer deposition, Genus will be hosting an Advanced Thin Films Technology Seminar during SEMICON West 99 at the Moscone Center from 8:30 a.m. to 1:00 p.m. on Wednesday, July 14 in room 272, West Mezzanine. The seminar addresses the “Red Zones” of the 1999 International Technology Roadmap for Semiconductors with prominent industry speakers.

About Genus

Founded in 1982, Genus, Inc. designs, manufactures and markets capital equipment and deposition processes for advanced semiconductor manufacturing. The Company’s thin film deposition products are used worldwide to produce integrated circuits for the data processing, communications, medical, military, transportation and consumer electronics industries. Genus’ customers include semiconductor manufacturers located throughout the United States, Europe and the Pacific Rim including Korea, Japan and Taiwan. Genus’ headquarters are located at 1139 Karlstad Drive, Sunnyvale, CA 94089, telephone (408) 747-7120; fax (408) 747-7199. For the most up-to-date company, product and financial information, visit Genus’ web site at <http://www.genus.com>.

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